

Appl. No. : known  
Filed : herewith

On Figure 2A, replace reference numeral "20" in the upper instance of the figure (leading to the plate) with --30--. Delete lead line and reference numeral "20" in the lower instance of the figure (leading to the lower end of shaft 22). Also, replace reference numeral "10" with --28--.

On Figure 2B, delete lead line and reference numeral "20" in the lower instance, leading to the lower end of shaft 22. Replace reference numeral "18" in the lower instance (leading to the susceptor) with --12--. Also, replace reference numeral "10" with --28--.

On Figure 2C, please add the reference numeral --28--.

If the Examiner approves of these changes, Applicant will incorporate the changes in a Submission of Formal Drawings.

**IN THE SPECIFICATION:**

On page 1, after the title, please add the following heading and paragraph:

--Reference to Related Application

The present application is a continuation of U.S. Application Serial No. 09/150,986, filed September 10, 1998, Patent No. 6,108,937

On page 6, lines 19-20, please replace "susceptor 16" with --susceptor 12--.

**IN THE CLAIMS:**

Please cancel Claims 1-52.

53. (Newly added) A processing reactor for high temperature treatment of substrates, the reactor comprising:

- a plurality of walls defining a chamber;
- a substrate support structure within the chamber;
- a heat exchange member;
- a movable element; and